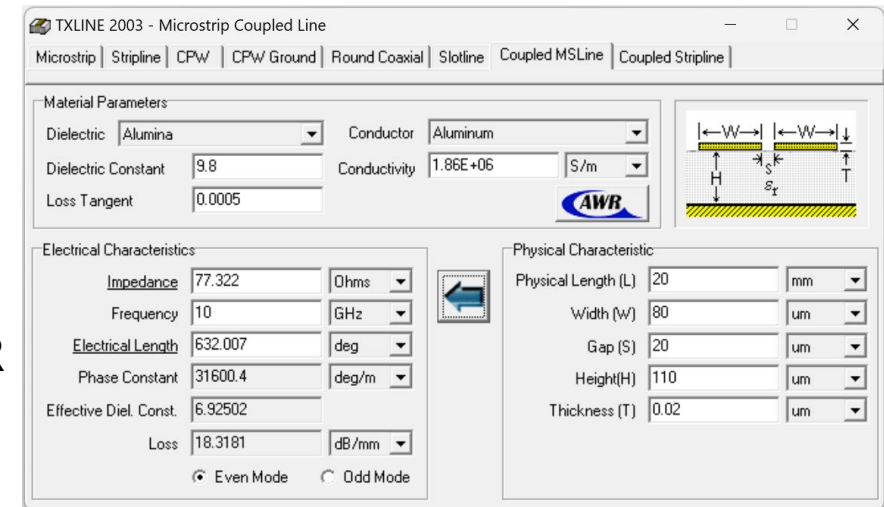
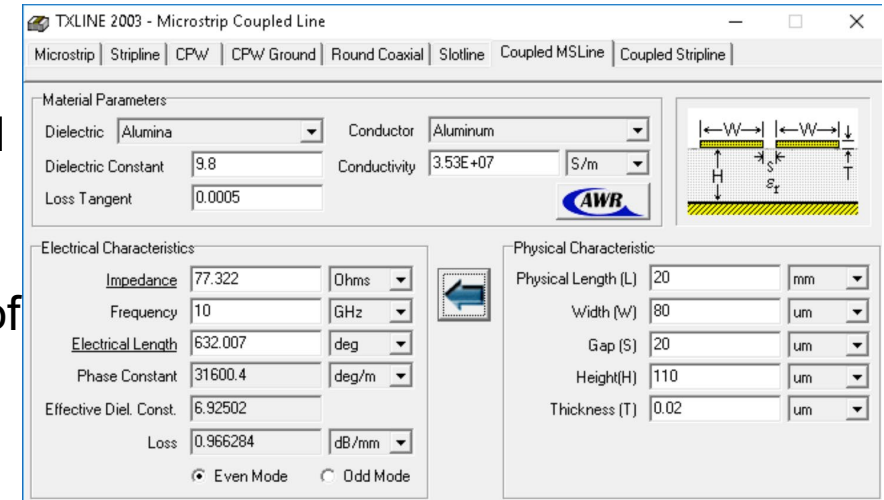


High strip resistivity and beam profile reconstruction a case study from CLEAR's TB 28-31/03/2023

- Typical strip resistance ($l=20\text{mm}$) for **Tomsk** sensors is measured to be **$6.7\text{k}\Omega$** for a strip, while **60Ω** for the **FBK** sensors.
- Typical strip even-mode impedance, assuming a signal rise time of 100ps , is approx. **77Ω** (93Ω) for the $110\mu\text{m}$ -thick ($150\mu\text{m}$) sensor.
- **Two key-points**
 1. high-strip resistivity implies signal attenuation (**loss**), whose intensity depends on the beam vertical position on the strip;
 2. lossy-line ($6.7\text{k}\Omega \gg 77\Omega$) means frequency-dependent termination: unproper matching and sig. **reflections**.
- **Case study:** signal from even/odd strips vs. beam pos. at CLEAR



Conclusions and open points

Conclusions

- High strip resistance – i.e., much bigger than strip impedance – should be **avoided**.
- Quality check of strip metallization is important to ensure the layer thickness is uniform and resistivity within specifications.
- Thicker metal layers are less affected by this issue.
 - ▶ FBK sensors OK

Open points

- Early sapphire sensors (UniversityWafers-Inc. sapphire crystal + strip metallization by Tomsk-University) are affected by such issue.
- Is it expected to have such high-resistance?
- How well can the layer thickness be controlled in the manufacturing process?

High strip resistivity and beam profile reconstruction a case study from CLEAR's TB 28-31/03/2023

- The **test** consists in moving the beam **along the strip** and measure the effect looking at the asymmetry between the beam charge from the reconstructed beam profile (gaus+const fit) using either the even or the odd strips

$$asymA \equiv \frac{(A\sigma)_{even} - (A\sigma)_{odd}}{(A\sigma)_{even} + (A\sigma)_{odd}}$$

- The signal attenuation depends on the path length $e^{-loss \Delta y}$. Readout of even strips signals is from the top, while odd from the bottom.

- If $(A\sigma)_{odd} \propto e^{-\alpha(\frac{d}{2}+y)}$ and $(A\sigma)_{even} \propto e^{-\alpha(\frac{d}{2}-y)}$, we expect

$$asymA = \tanh(\alpha y) = \alpha y - \frac{(\alpha y)^3}{3} + O((\alpha y)^5)$$

a line with positive slope, as observed!

(notice we have $(\alpha y) \sim 10^{-2}$)

